

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

SAH
#SA
4-8-02

In re application of

Isao NAKATANI

Attn: BOX PCT

Serial No. ~~NEW~~

Docket No. ~~2001-0701A~~

Filed June 1, 2001

DRY ETCHING

[Corresponding to PCT/JP99/06761

Filed December 2, 1999]

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents,
Washington, DC 20231

Sir:

Please amend the above-identified application as follows:

IN THE SPECIFICATION

Please amend the specification as follows:

After the title of the invention please insert the following:

This application is a 371 application of PCT/JP99/06761 filed December 2, 1999.

IN THE CLAIMS

Cancel, without prejudice to the subject matter involved, claims 1-4.

Please add the following new claims:

5 (New). A dry etching method comprising etching a metallic surface of copper, silver, gold, or an alloy containing as a main component at least one of these metals by plasma of an etching gas containing at least nitrogen oxide and hydrogen, or a hydrogen-containing compound free from halogen atoms while being reacted with the plasma.